

**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

(Use several sheets if necessary)

Attorney Docket No.:

8038-1062

Application No.

NEW NATIONAL PHASE

Applicant:

Takayuki SHIMAMUNE et al.

Filing Date:

March 14, 2005

Group Art Unit:

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing date (if appropriate)

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	2003-242016	12/3/2003	JAPAN				
	2003-95633	4/3/2003	JAPAN				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

D.A. SEIFERT, PILOT-SCALE DEVELOPMENT OF THE ZINC REDUCTION PROCESS FOR PRODUCTION OF HIGH-PURITY SILICON, AICHE SIMPOSIUM SERIES, 1982, NO. 216, VOL. 78, PAGES 104-115

EXAMINER: /Elias Ullah/

DATE CONSIDERED

01/02/2009

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* English language abstract provided for the Examiner's convenience

BC/crt

Y&T September 29, 2004

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /E.U./